

Version of Amendments With Markings to Show Changes Made

1. (Once Amended) A device for generating a plurality of electron beams comprising:
- e) a source of radiation; and,
 - f) a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation; and,
 - g) a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation.
6. (Once Amended) An device as in claim [5] 1 wherein said spatial light modulator is a micromirror array.
7. (Once Amended) An electron beam lithography system comprising:
- d) a source of radiation; and,
 - e) a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation; and,
 - f) a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation; and
 - h) an electron beam optical column having a position so as to receive said plurality of electron beams and to direct said plurality of electron beams onto a target.
12. (Once Amended) A system as in claim [11] 7 wherein said spatial light modulator is a micromirror array.
13. (Once Amended) A method of producing a plurality of electron beams comprising:
- c) directing radiation onto a spatial light modulator, thereby modulating said radiation; and,

- d) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams.

18. (Once Amended) A method as in claim [17] 13 wherein said spatial light modulator is a micromirror array.

19. (Once Amended) A method of performing lithography with multiple beams of electrons comprising:

- d) directing radiation onto a spatial light modulator, thereby modulating said radiation; and,
- e) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams; and,
- f) directing said plurality of electron beams onto [the] an acceptance region of an electron beam optical column, producing thereby a plurality of electron beams impacting a target located at the target end of said electron beam optical column.

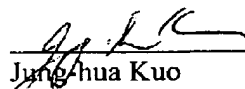
24. (Once Amended) A method as in claim [23] 19 wherein said spatial light modulator is a micromirror array.

CONCLUSION

Applicants believe that all pending claims are allowable and respectfully request a Notice of Allowance for this application from the Examiner. Should the Examiner believe that a telephone conference would expedite the prosecution of this application, the undersigned can be reached at the telephone number set out below.

In the unlikely event that the transmittal letter accompanying this document is separated from this document and the Patent Office determines that an Extension of Time under 37 CFR 1.136 and/or any other relief is required, Applicant hereby petitions for any required relief including Extensions of Time and/or any other relief and authorizes the Commissioner to charge the cost of such petitions and/or other fees due in connection with the filing of this document to Deposit Account No. 50-1217 (Order No. AMATP010).

Respectfully submitted,



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